

## Conduction Mechanism Analysis and Oscillation Phenomena of Low Voltage ZnO Varistor

12-11-4

Kyung-Uk Jang\*, Myung-Ho Kim\*, Woo-Heon Park\*\*\*, Joon-Ung Lee\*\*

### Abstract

ZnO varistors have an excellent non-linearity and a large surge-energy absorption capability. For these reasons, the ZnO varistors are widely used to protect electrical/electronic circuits from an abnormal surge and/or noise signal. In order to obtain the low-voltage varistor with randomly distributed large seed grain within bulk, the ZnO varistors are made by a new three-composition seed grain method. From the I-V characteristics of the fabricated varistors, the knee voltage of varistors with the seed grain 5wt% is 5 V. We may also present a carrier oscillation properties for the low-voltage varistor fabricated by the new method of three-composition seed grain.

**Key Words(중요용어)** : ZnO varistor, Low voltage varistor, Seed grain, 3-composition seed grain, I-V characteristics

### 1. INTRODUCTION

ZnO varistors are nonlinear devices which are commonly used for a suppression of transient pulses and surges in electronic devices or power lines<sup>(1)</sup>.

The current-voltage (I-V) characteristic of varistor is strongly nonlinear. At low voltage, varistor is highly resistive more than  $10^{10} \Omega\text{-cm}$ , while at the high electric field the current acrossing the varistor can be very large as described by the empirical equation<sup>(2)</sup>

$$I = (KV)^\alpha \quad (1)$$

where, K is geometric constant of sample,  $\alpha$  a nonlinear coefficient. The nonlinear coefficient of ZnO varistor shows up to above  $\alpha$

50. A knee voltage of the varistor can be generally written as<sup>(3)</sup>

$$V = N_g \cdot V_g \quad (2)$$

where,  $N_g$  is the numbers of ZnO grains in series within the sample and  $V_g$  the knee voltage per grain boundary. Therefore, the microstructure of low voltage ZnO varistor has to be fairly large size of grain in order to obtain the low voltage varistor<sup>(4)</sup>.

In this paper, it is introduced that a distribution of large grain size in ZnO for low voltage varistor is due to discontinuous grain growth and can be narrowed by using a 3-composition seed grain method. We also present the fact that the conduction mechanism of the fabricated varistor can be divided into the three region. The conduction properties of varistor, which was measured in the temperature range of 30~120°C with the current range of  $10^{-8} \sim 10^2 \text{A/cm}^2$ , was divided into the three region having different conduction mechanisms as the current was increased : The region I (say, leakage-current region) in  $E_{int} < 25 \text{ MV/m}$  shows an

\* : Kyungwon College, San 65, Bokjung-dong, Soojong-gu, Songnam-shi, Korea

\*\* : Next President of KIEEME

\*\*\* : NARA ENGINEERING CONSULTANT  
1999년 1월 29일 접수, 1999년 9월 17일 심사완료

Ohmic conduction. The region II (say, pre-breakdown region) in the  $25 < E_{int} < 70$  MV/m can be explained by the Poole-Frenkel and Schottky conduction mechanism, and the region III (breakdown region) in  $E_{int} > 70$  MV/m is dominated by the tunneling effect.

The oscillation phenomena of carriers in current-voltage characteristics below the knee voltage are explained by the transient flow of nontrapped carriers group in the trap level of intergranular layer, surface state and/or depletion layer<sup>(6)</sup>.

In particular, the current oscillation phenomena are hardly shown in the high electric field. It is why that the injected carriers from both electrodes are directly transported from the conduction band of forward biased ZnO grain into the reverse biased ZnO grain through the intergranular layer, since the trap level in the electric field above the knee voltage is mostly filled.

2. EXPERIMENT

Fine powder composed with ZnO(97 mol%), BaCO<sub>3</sub>(2.5 mol%) and TiO<sub>2</sub>(0.5 mol%) were pressed at 450 kg/cm<sup>2</sup>, and sintered in the furnace at 1400 °C for 10 hrs.

After those processes, the sintered bodies were washed in the boiled water, and then four kinds of different seed grain were obtained.

The compounds mixed with ZnO(98 mol%), Bi<sub>2</sub>O<sub>3</sub>(1 mol%), CoO(0.5 mol%) and MnO<sub>2</sub>(0.5 mol%), of which the seed grain contents are 0, 5, 10, 20 and 40 wt%, were pressed at 450 kg/cm<sup>2</sup>. The pressed bodies were sintered in the furnace at 1300 °C for 2 hrs. Then the sintered bodies were polished with silicon carbide abrasive of 1200 meshes into the thickness of 1.0 mm. The contacts were done with the silver paste to the surface of sample for 12 mm in diameter and 1 mm in thickness. The fabrication procedure of sample is given in Fig. 1.

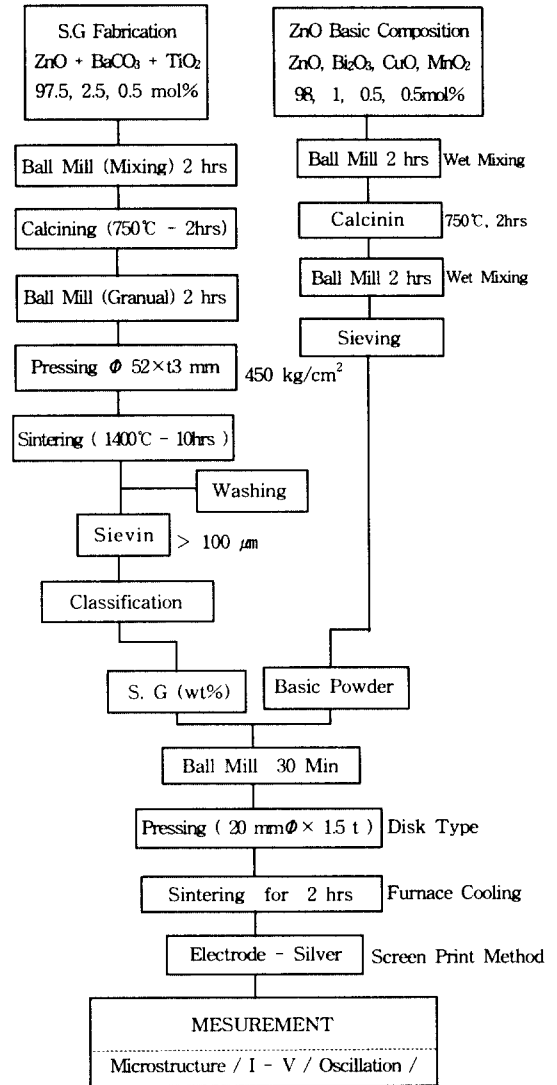


Fig. 1. The fabrication procedure of sample.

Electrical measurement of the sample was performed in the current range from 10<sup>-8</sup> to 10<sup>2</sup> A/cm<sup>2</sup> within the temperature range from 30 to 120 °C, as shown in Fig. 2.

The carrier oscillation measurement of sample was performed with the amplifier (NF Electronic Instrument bx-31, USA), power supply(Keithley 237, USA) and oscilloscope(Yokogawa PL 2140B, JAPAN), as

shown in Fig. 3.

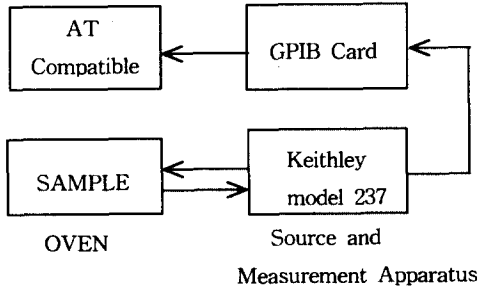


Fig. 2. Block diagram for I-V measuring apparatuses.

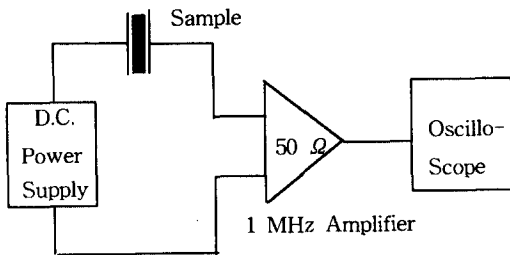


Fig. 3. Measurement of oscillation phenomena.

### 3. RESULTS AND DISCUSSION

Fig. 4 shows the current-voltage characteristics of the samples with the various contents of seed grain, and Fig. 5 suggests the nonlinear coefficient  $\alpha$  was decreased from 30 to 11. The values of  $\alpha$  may largely depend on the existence of intrinsic pore and a third phase in the sample<sup>(6, 11)</sup>. Fig. 6 shown the knee voltage of ZnO varistor as a function of seed grain contents. It can be concluded from the microstructure of the samples that the phenomena are considered by a correlation between the different grain sizes of base powder and the seed grains as well as the different radius of curvature.

The pore and the secondary recrystalline in the sample seem to grow due to increase

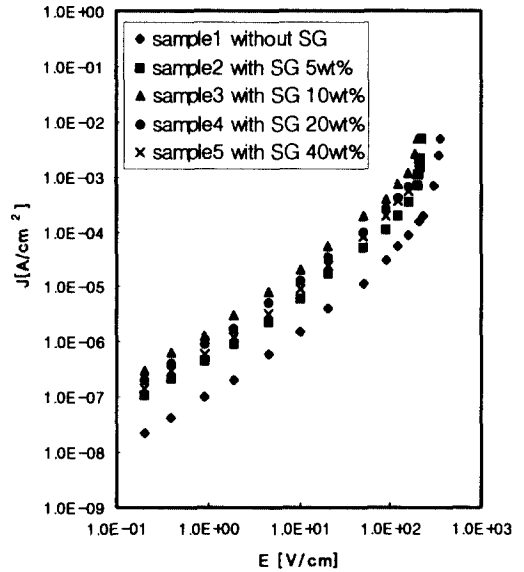


Fig. 4. Current-Voltage characteristics of ZnO varistor with the contents of the seed grain.

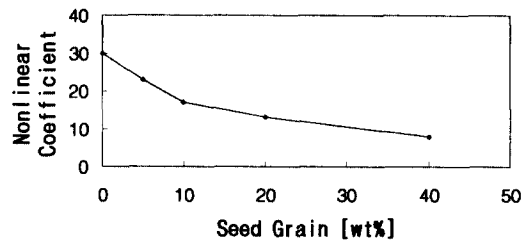


Fig. 5. Nonlinear coefficient of ZnO varistor as a function of the seed grain content.

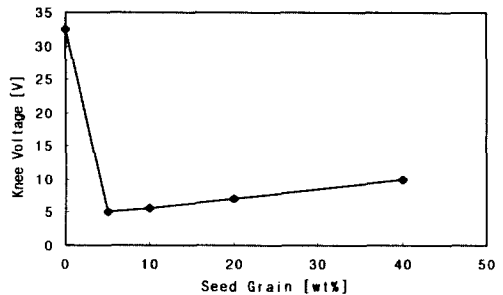


Fig. 6. Knee voltage of ZnO varistor as a function of the seed grain content.

in the seed grain content. The mean size of seed grain is increased by secondary recrystallization during sintering. The optimized content rate of seed grain in the sample was 5 wt %.

The conduction mechanism of low-voltage varistor with 5 wt% content of seed grain was classified by the three regions with different mechanism as shown in Fig. 7.

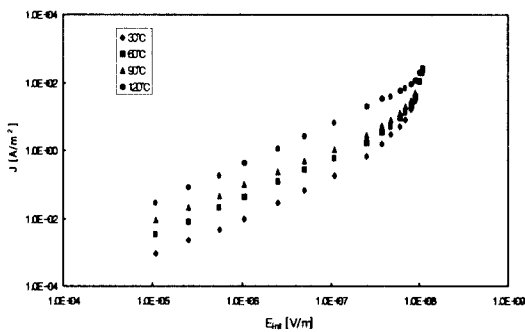


Fig. 7. Current-voltage characteristics of ZnO varistor with the content of seed grain 5 wt% for several different measuring temperatures.

Fig. 7 show the temperature dependent current-voltage characteristics of the specimen added 5wt% of seed grain. As seen in the Fig. 7, the knee voltage is  $5V_{(1mA/cm²)}/mm$ , and the temperature dependence is relatively large at low electric-field region, but hardly seen at about high electric-field region. The knee voltage of varistor is depended on the breakdown voltage of intergranular layer and the number of its<sup>(9)</sup>. In Fig. 7, when the thickness of specimen is 1 mm and the size of grain is tens of  $\mu m$ , it is not describe that the knee voltage of specimen is  $5V_{(1mA/cm²)}/mm$ . If the large seed grain was added in the specimen, these results could be explained by the large seed grain with low resistivity distributed randomly, which is conduction path, because the knee voltage is independent on the effective mean size of

seed grain and ZnO grain<sup>(6)</sup>. When the specimen added seed grain is sintered, the knee voltage of varistor is lowered because the grain size is depended on the secondary growth during the large seed grain and raw ZnO powder is sintered<sup>(7)</sup>. It is known that the current is increased as the temperature of the specimen is increased, and also the current density is linearly proportional to the strength of the electric field.

The current density increases nonlinearly at the transition region above the low-electric field. It is considered that the current density increases due to the electron injected from electrode according to the increment of temperature. And then, we also know that the rapid-varying region in I-V characteristics is not affected by the measured temperature at all.

Therefore, we explain I-V characteristics with three regions according to conduction process in order to represent the conduction mechanism of varistor added 3-composition seed grain. First, the leakage-current region, that is, the low current ohmic region A, the nonlinear conduction region B and the the breakdown region C of varistor appear sequentially. Also, so as to analyze the above conduction mechanisms, we must consider the electric field  $E_{int}$  instead of the electric field applied specimen because the depletion layer really acts as an insulator<sup>(8)</sup>. So, we obtained  $E_{int}$  from the depletion layer thickness of 200A calculated in the result of C-f characteristics<sup>(12)</sup>.

As known from Fig. 7, the nonlinear coefficient  $\alpha$  and its temperature dependence are different in prebreakdown and breakdown region. Therefore, the electrical conduction mechanism of the low-voltage ZnO varistor can't be described with one conduction mechanism. So, we could analyze the 3 region in Fig. 7 with 3 conduction mechanisms.

(1) Conduction mechanism

The conduction current depends on the temperature and electric stress. Results of measurements are given in Fig. 7, which shows the conduction current of the ZnO varistor at constant temperature(30 and 120 °C) as a function of the electric field stress.

The relationship between conduction current and electric field is not linear, i.e., nonohmic. Three different regions, region I, II, and III, may be distinguished in the diagram<sup>(6)</sup>. Region I is below 25 MV/m, region II is in between 25 MV/m and 70 MV/m, and region III is above 70 MV/m.

1) Leakage current region,  $E_{int} < 25$  MV/m

Leakage current is important factor in causing the degradation of varistor, because it always flows before operation of varistor.

The Ohmic conduction mechanism in ZnO varistor has been studied by many researchers<sup>(6)</sup>. L. M. Levinson found that in the Ohmic region of conduction of ZnO varistor the diffusion current generally may be disregarded because it is such a small value<sup>(6)</sup>.

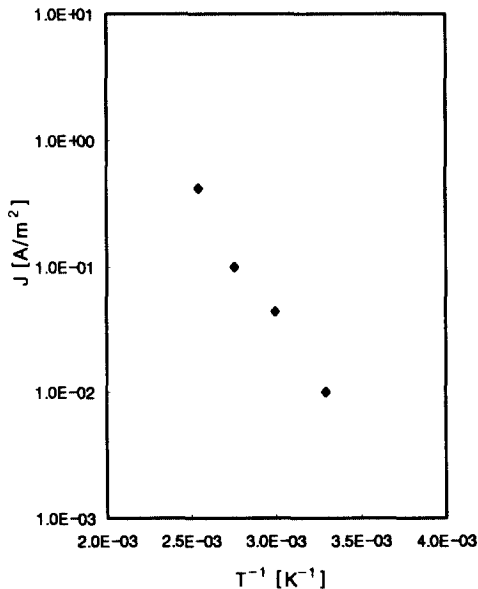


Fig. 8. Plot of log J vs. reciprocal temperature in region I.

Our results in region I, electric field stress below 25MV/m, support the Ohmic conduction mechanism theory.

Fig. 8 is the Arrhenius plots of log J at steady state vs. 1/T for region I of Fig. 7. The activation energy obtained from the diagram is 0.36eV. Similar values have been obtained by other workers.

The carriers attributed to the conduction current may be due to ionic impurities. The carriers of impurities may be formed in the intergranular layers during the fabrication process.

2) Prebreakdown region,  $25 < E_{int} < 70$  MV/m

Various theories were proposed by many researchers in the conduction mechanism of region II<sup>(1,3)</sup>. In Fig. 7, prebreakdown region (region II) is analyzed by the Poole-Frenkel emission theory considering the extrinsic level or trap between intergranular layers, because it has larger dependence of the electrical field than the leakage current region. Fig. 9 was obtained from Fig. 7, and shows the linear relationship between the log  $\sigma$  and  $E^{1/2}$ .

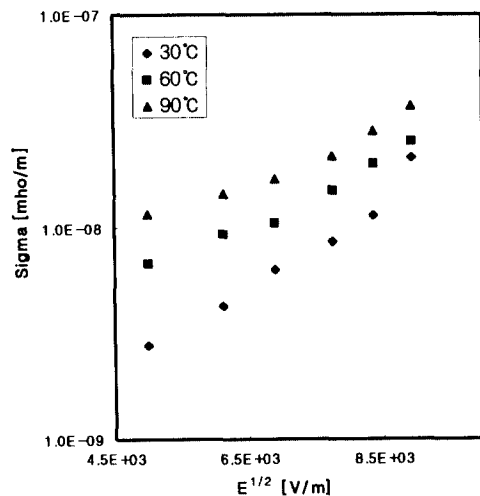


Fig. 9. Plot of log  $\sigma$  vs.  $E^{1/2}$  in region II.

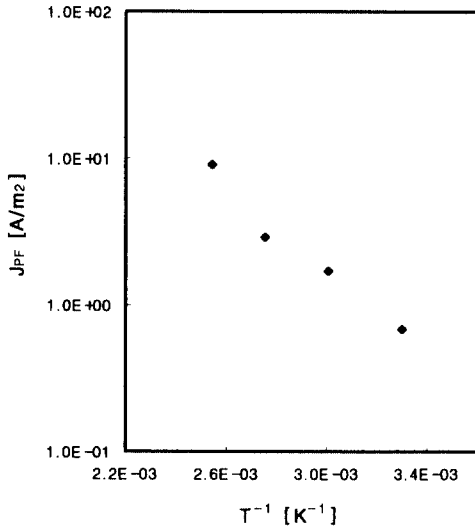


Fig. 10. Plot of  $J_{PF}$  vs. reciprocal temperature in Poole-Frenkel region.

Thus Poole-Frenkel or Schottky conduction mechanisms may be operative in this region. Charge injected from a metal and ZnO grain to the intergranular layer of insulator at medium fields may take place by field-assisted thermionic emission, a process known as Schottky emission. The force exerted on a particle at a distance  $x$  from the interface is given by

$$F = eE - \frac{e^2}{4\pi\epsilon_0\epsilon_r(2x)^2} \quad (3)$$

The work done on the particle is

$$W = -\int F dx = -eEx + \frac{e^2}{4\pi\epsilon_0\epsilon_r} 4x + \varphi \quad (4)$$

The constant of integration has been chosen so that  $W \equiv \psi$  at a large distance from the electrode under zero applied field. For nonzero field,  $W$  has a maximum value  $\psi_{app}$  at the point where  $F=0$ . This gives the result

$$\psi_{app} = \psi - \beta_s E^{\frac{1}{2}} \beta_s = \left( \frac{e^3}{4\pi\epsilon_0\epsilon_r} \right)^{\frac{1}{2}} \quad (5)$$

Consequently, the current density drawn over this barrier is

$$J_s = A T^2 \exp\left(-\frac{\psi}{kT}\right) \exp\left(\frac{e^3}{4\pi\epsilon_0\epsilon_r}\right) \quad (6)$$

Where  $A = 12 \times 10^5 [A/m^2 k^2]$ ,  $\psi$  is the potential barrier,  $\epsilon_r$  is the dielectric constant at high frequency, and  $T$  is the absolute temperature. When electric field interacts with the coulombic potential barrier of the trap, the height of the barrier is lowered. This process known as the Poole-Frenkel effect is the bulk analogous of the Schottky effect at an interfacial barrier. Since the potential energy of an electron in a coulombic field,  $-e^2/4\pi\epsilon_0\epsilon_r$ , is four times that due to image force effects. The Poole-Frenkel attenuation of a coulombic barrier,  $\psi_{PF}$ , in a uniform electric field is twice that due to the Schottky effect at a neutral barrier

$$\Delta\psi_{PF} = \left( \frac{e^3}{\pi\epsilon_0\epsilon_r} \right)^{\frac{1}{2}} E^{\frac{1}{2}} = \beta_{PF} E^{\frac{1}{2}} \quad (7)$$

$$\beta_{PF} = \left( \frac{e^3}{\pi\epsilon_0\epsilon_r} \right)^{\frac{1}{2}}$$

Thus, the conductivity is field-dependent and the current density drawn over this barrier is

$$J_{PF} = J_0 \exp\left(-\frac{\psi}{2kT}\right) \exp\left(\frac{\beta_{PF} E^{\frac{1}{2}}}{2kT}\right) \quad (8)$$

To determine whether it is Poole-Frenkel or Schottky process, the slope of the straight lines in Fig. 9 are compared with the theoretically calculated slopes  $\beta_{th}$  from the Schottky relationship:  $\beta_s = (e^3/4\pi\epsilon_0\epsilon_r)^{\frac{1}{2}}$ .

In our sample, the theoretical value ( $\beta_{th}$ ) of  $\beta_s$  is  $1.56 \times 10^{-24}$ . If the value of  $\beta$  obtained from the slope is close to that of  $\beta_{th}$  obtained theoretically, the process is that of Schottky emission.

If the value of  $\beta$  obtained from the slope is double that of  $\beta_{th}$ , the process is that of Poole-Frenkel emission. From the slope of straight line in Fig. 9, we found that  $\beta_{PF}$  is  $3.4 \times 10^{-24}$  and  $\epsilon_r$  is 13, respectively.

The Arrhenius plot for a field of 44MV/m is shown in Fig. 10. The barrier height value is  $\phi = 0.7$  eV.

In our study, the value of  $\beta_{PF}$  is double that of the theoretically calculated  $\beta_{th}$  ( $1.56 \times 10^{-24}$ ) and  $\beta_s$  ( $1.68 \times 10^{-24}$ ) which was obtained in the end part of region II ( $E_{int}$  between 50~70MV/m) :

$\beta_{PF} = 3.4 \times 10^{-24} \approx 2 \times 1.56 \times 10^{-24} (2 \beta_{th}) \approx 2 \times 1.68 \times 10^{-24} (2\beta_s)$ . Therefore, the conduction mechanism in region II is likely to be dominated by the Poole-Frenkel effect. In this region, either the Poole-Frenkel or Schottky conduction mechanism may be operative as in region I, and shows the relationship of straight line between the  $\log \sigma$  and  $E^{1/2}$ . The slope  $\beta_s$  obtained in this region is close to  $\beta_{th}$  ( $1.56 \times 10^{-24}$ ) calculated theoretically, and equal to half the slope  $\beta_{PF}$  ( $3.4 \times 10^{-24}$ ) for the Poole-Frenkel effect.

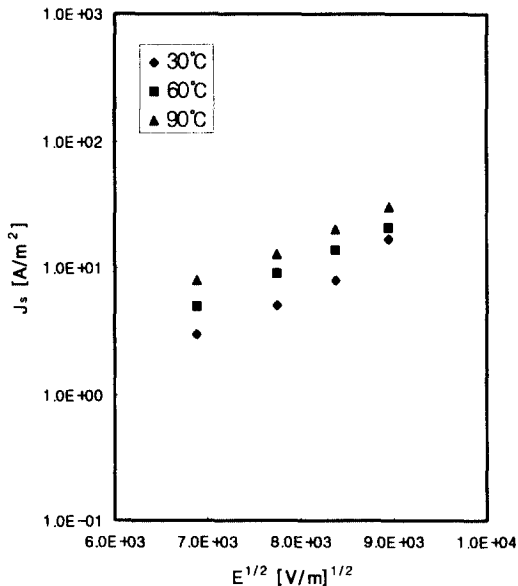


Fig. 11. Plot of  $\log J_s$  vs.  $E^{1/2}$  in region II.

The donor level,  $\phi$ , the potential barrier between the metal contact and dielectric material is obtained from the relationship of

$\log(J_s/T^2)$  vs.  $1/T$  at the applied field of 60MV/m(Fig. 12). The donor level obtained is  $\phi = 0.24$  eV at an applied field of 60MV/m in Schottky region.

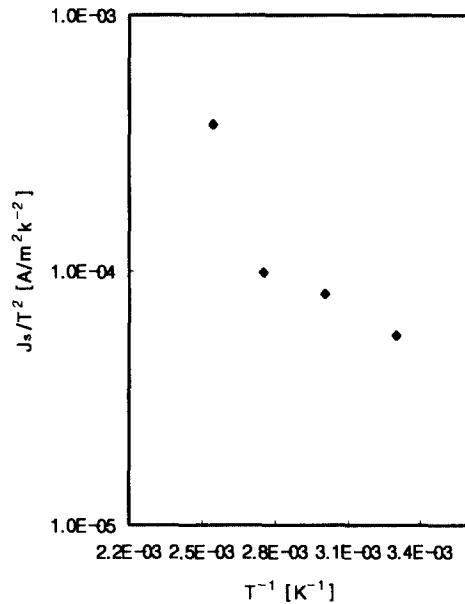


Fig. 12. Plot of  $\log J_s$  vs. reciprocal temperature.

### 3) Breakdown region, $E_{int} > 70$ MV/m

The conduction mechanism of breakdown region independenting on the ambient temperature has been proposed several theories so far, that is, space charge limited current, schottky emission theory and electron avalanche theory and so on. But these theories are not efficiently explained the experimental phenomena in that region. Therefore, we apply the tunnel theory to the breakdown region. The magnitude of the knee voltage is considered with Fowler-Nordheim tunneling effect from the relation between the microstructure and equivalent circuit of the sample.

The increase in conduction current in region III (Fig. 7) is larger than expected

from the Schottky effect in region II. At very high fields in the ZnO varistor, the potential barrier becomes very thin and a different mechanism comes into play. Electrons injected into intergranular layer from the electrode and ZnO grain pass through thin potential barriers despite of having insufficient energy to surmount them ; this is known as tunneling. When this occurs at the interface barrier it is known as Fowler-Nordheim injection where the current is

$$J_{FN} = A_1 E^2 \exp(-B/E) \tag{9}$$

where  $A_1 = 2.2 e_2 / 8\pi h \psi$  and  $B_2 = -8\pi d(2m)^{1/2} \psi^{3/2} / 3he$ .  $m$  is effective electron mass and  $h$  is Plank constant. Fig. 13 shows the  $\log(J_{FN}/E^2)$  vs.  $1/E$  plot, and from the slope the potential barrier  $\phi = 0.3$  eV was obtained. Generally, the tunneling current depends strongly on the applied field and is independent of temperature<sup>(5, 9)</sup>. However, in our experimental results the tunneling current slightly depends on temperature because the carriers first penetrate from the metal electrode into potential barrier and then the penetrated carriers are released by thermal excitation into the conduction band of ZnO. Both thermionic and field emission occur simultaneously.

The barrier height in each region may be

dominated by the electric field and temperature.

Therefore, the conduction mechanism in each region is different.

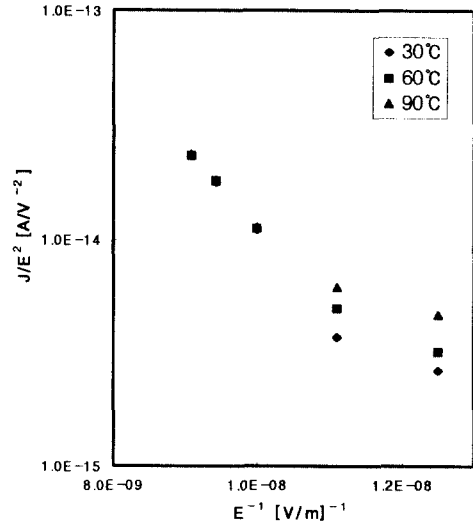
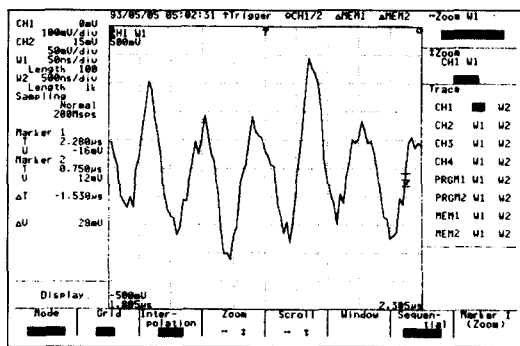


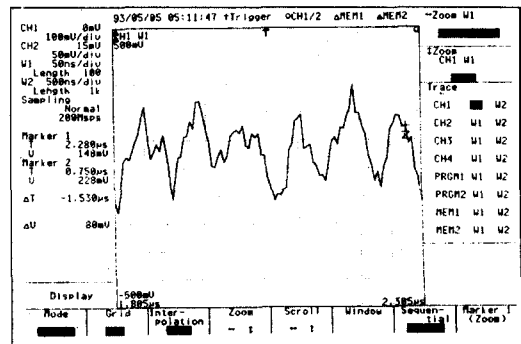
Fig. 13. Plot of the  $\ln (J/E_{int}^2)$  and  $1/E_{int}$  in the breakdown region.

(2) Current oscillation phenomena and their mobility

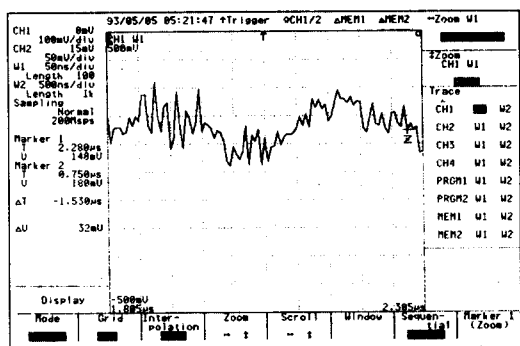
Fig. 14 shows the current-voltage oscillation phenomena of the specimen measured at 30°C. As shown in Fig. 14, it is known that



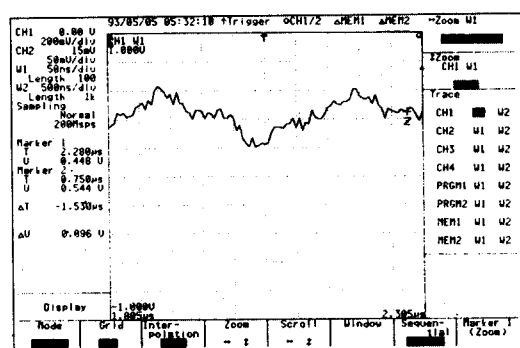
(a) Electric field  $5 \times 10^5$  [V/m]



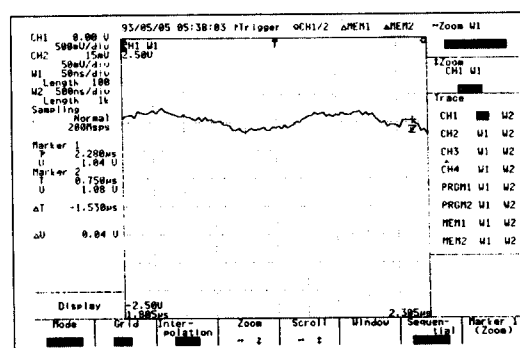
(b) Electric field  $2 \times 10^7$  [V/m]



(c) Electric field  $4 \times 10^7$  [V/m]



(d) Electric field  $6 \times 10^7$  [V/m]



(e) Electric field  $8 \times 10^7$  [V/m]

Fig. 14. Current oscillation phenomena observed with oscilloscope.

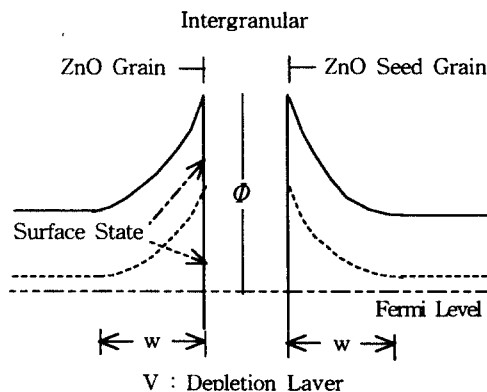
the oscillation amplitude of current decreases and the oscillation frequency increases, when the applied voltage increases from

region I of ohm region to region III of breakdown region.

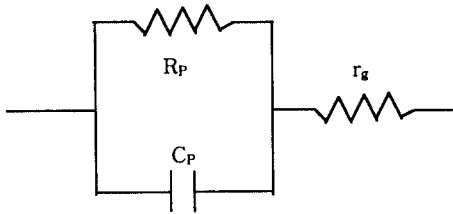
Fig. 15(a) is equivalent model considering intergranular layer between ZnO grain and ZnTi seed grain in microstructure of the specimen. In Fig. 15(b),  $r_g$  is a resistance of ZnO grain,  $C_p$  and  $R_p$  is equivalent capacitance and resistance of interface and depletion layer, respectively.

As for the most of injection electron in the electric field under breakdown region of varistor is filled in the trap level of intergranular layer, and then the injection electron does not influence on conduction, current is low in the low electrical field region. Also, part of the nontrapped injection electron which is accumulated in the intergranular layer has electrostatic force with the form of electron group. As increasing the electric field, the current oscillation phenomena is appeared with the junction non-equilibrium of electrostatic force between intergranular layer and depletion layer.

In the breakdown region, most of injected electron drift from conduction band in forward bias grain to conduction band in reverse bias grain without delay time, because the accumulative site of electron group does not exist in trap level of the intergranular layer as progressive accumulation of electron in the trap level<sup>(9)</sup>.



(a) Equivalent model in the intergranular layer



(b) Equivalent electrical model

Fig. 15. Equivalent model of ZnO varistors.

As the electron injected in forward bias is directed tunneling to reverse bias, current oscillation is hardly appeared in the electric field above breakdown region of varistor.

These phenomena are appeared in not only varistor but also in insulator and semiconductor. Particularly, T. Yasukawa reported on the current oscillation phenomena in the conduction process of CdS<sup>(10)</sup>.

The relation between carrier mobility( $\mu$ ) and period(T) is calculated using the following equation.

$$\mu = \frac{d}{T \cdot E} [m^2/V \cdot s] \tag{10}$$

where, the thickness of intergranular layer, d is 200Å, and E is the electric field intensity obtained in equivalent model. Carrier mobility will be calculated with sampling method from test results.

Fig. 14 shows the current oscillation phenomena in the various electric field of region I, region II and region III, respectively. There are simultaneously group oscillation

and irregular fine oscillation in these figures.

It is supposed that the origin of irregular fine oscillation is to drift a part of non-trapped injection electron from conduction band in forward bias grain to conduction band in reverse bias grain.

As shown in Fig. 16 (a)~(f), it is supposed that the injected electrons are accumulated in the intergranular layer on the effect of image charge, and then drift to the conduction band of reverse bias grain with increasing electric field intensity<sup>(9)</sup>.

These phenomena are the origin of group oscillation. Fig. 14 shows that the oscillation amplitude is proportional to the number of accumulated electron.

The amplitude of group oscillation in the low electric field intensity of region I is larger than the irregular fine oscillation, but it is scarcely different in the high electric-field region III.

As a result, the injected electrons in the breakdown region directly drift from conduction band in forward bias grain to conduction band in reverse bias grain, because the accumulative site of electron group does not exist in the trap level of the intergranular layer as increasing the applied voltage.

Table 1 is shown the value of mobility obtained in each region using the equation (10). As shown in Table 1, the mobility of irregular fine oscillation is independent of electric field, but the mobility of group oscillation is smaller with increasing electric field intensity. Because of increased applied voltage, the number of accumulated group

Table 1. Mobility of carriers in the intergranular model

| $E_{int}$<br>[V/m]                                | $5 \times 10^5$   | $1 \times 10^7$   | $2 \times 10^7$   | $3 \times 10^7$      | $4 \times 10^7$      | $5 \times 10^7$      | $6 \times 10^7$    | $7 \times 10^7$      | $8 \times 10^7$    | $1 \times 10^8$      |
|---|-------------------|-------------------|-------------------|----------------------|----------------------|----------------------|--------------------|----------------------|--------------------|----------------------|
| Fine oscillation<br>mobility [ $m^2/V \cdot s$ ]  | $2.9 \times 10^7$ | $1.6 \times 10^8$ | $9 \times 10^8$   | $7.1 \times 10^8$    | $5.3 \times 10^8$    | $3.2 \times 10^8$    | $3 \times 10^8$    | $3 \times 10^8$      | $2 \times 10^8$    | $1.6 \times 10^8$    |
| Group Oscillation<br>mobility [ $m^2/V \cdot s$ ] | $4.9 \times 10^8$ | $2.4 \times 10^9$ | $1.1 \times 10^9$ | $2.4 \times 10^{10}$ | $1.7 \times 10^{10}$ | $1.5 \times 10^{10}$ | $1 \times 10^{10}$ | $9.3 \times 10^{11}$ | $8 \times 10^{11}$ | $5.3 \times 10^{11}$ |

electron is decreased due to the effect of image charge, and the characteristics of varistor will be appeared in sample for fastly distortion of junction, decreasing priode and amplitude due to the transportation of group electron.

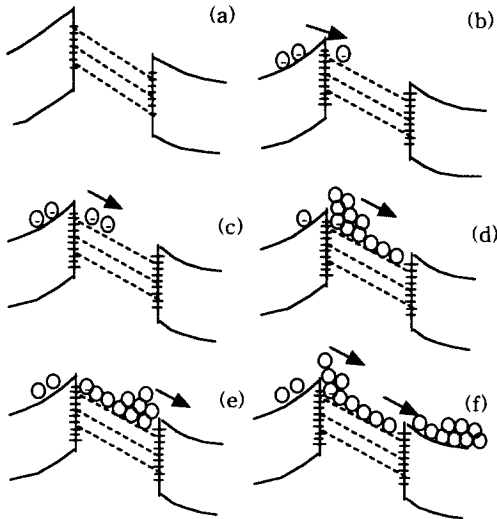


Fig. 16. The oscillation model of conduction in the intergranular layer.

#### 4. CONCLUSIONS

The method making low-voltage ZnO varistors with the 3-composition seed grain of extra grain size was reported in this paper.

The results of the conduction mechanism and the oscillation characteristics of carrier for non-ohmic ZnO varistor fabricated by 3-composition seed grain method could be obtained as follows :

1. The knee voltage and nonlinear coefficient  $\alpha$  of the specimen with 3-composition seed grain of 5 wt % are 5 V and 22, respectively.
2. The conduction mechanism is mainly governed by the thermoionic emission below the knee voltage but also the

field emission of double Schottky model at above the knee voltage. The calculated activation energy and trap level of those region are 0.36 and 0.70 eV, respectively.

3. The conduction mechanism for the non-linear region above the knee voltage can be analyzed by the Fowler-Nordheim tunneling effect. The barrier height of the model in this region is 0.26 eV.
4. The oscillation amplitude of carrier is inversely propotional to the applied voltage.
5. The mobility of irregular fine oscillation is  $2.9 \times 10^{-4} \text{m}^2/\text{V} \cdot \text{s}$  at  $5 \times 10^5 \text{V/m}$  in this region, it is independent to the applied voltage.
6. The mobility of group oscillation is  $4.9 \times 10^{-4} \text{m}^2/\text{V} \cdot \text{s}$  at  $5 \times 10^5 \text{V/m}$  in this region, it decreases with increasing applied voltage.

It is concluded that the method by three-composition seed grain would be better than any other methods, to make varistors with knee voltage below  $5 \text{ V}_{(1\text{mA/cm}^2)}$ . The conduction properties of ZnO varistor may be determined by height of potential barrier. The characteristics of varistor will also be appeared with oscillation for the fast distortion of junction, decreasing the priode and the amplitude due to transportation of group electron.

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